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(54) **A heat mode sensitive imaging element for making positive working printing plates.**

Wärmeempfindliches Aufzeichnungselement zur Herstellung von positiv arbeitenden
Flachdruckformen

Élément thermosensible pour l'enregistrement de l'image pour la fabrication de plaques
lithographiques positives

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EP-A- 0 573 092	EP-A- 0 823 327
FR-A- 1 561 957	GB-A- 1 154 568
GB-A- 1 155 035	GB-A- 1 160 221
GB-A- 1 208 415	GB-A- 1 245 924
US-A- 5 466 557	US-A- 5 641 608

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Description

FIELD OF THE INVENTION

5 [0001] The present invention relates to a heat mode imaging element for preparing a lithographic printing plate comprising an IR sensitive top layer.
More specifically the invention is related to a heat mode imaging element for preparing a lithographic printing plate with a higher scratch resistance.

10 BACKGROUND OF THE INVENTION

[0002] Lithography is the process of printing from specially prepared surfaces, some areas of which are capable of accepting lithographic ink, whereas other areas, when moistened with water, will not accept the ink. The areas which accept ink form the printing image areas and the ink-rejecting areas form the background areas.

15 [0003] In the art of photolithography, a photographic material is made imagewise receptive to oily or greasy inks in the photo-exposed (negative-working) or in the non-exposed areas (positive-working) on a hydrophilic background.

[0004] In the production of common lithographic printing plates, also called surface litho plates or planographic printing plates, a support that has affinity to water or obtains such affinity by chemical treatment is coated with a thin layer of a photosensitive composition. Coatings for that purpose include light-sensitive polymer layers containing diazo compounds, dichromate-sensitized hydrophilic colloids and a large variety of synthetic photopolymers. Particularly diazo-sensitized systems are widely used.

20 [0005] Upon imagewise exposure of the light-sensitive layer the exposed image areas become insoluble and the unexposed areas remain soluble. The plate is then developed with a suitable liquid to remove the diazonium salt or diazo resin in the unexposed areas.

25 [0006] Alternatively, printing plates are known that include a photosensitive coating that upon image-wise exposure is rendered soluble at the exposed areas. Subsequent development then removes the exposed areas. A typical example of such photosensitive coating is a quinone-diazide based coating.

[0007] Typically, the above described photographic materials from which the printing plates are made are camera-exposed through a photographic film that contains the image that is to be reproduced in a lithographic printing process. Such method of working is cumbersome and labor intensive. However, on the other hand, the printing plates thus obtained are of superior lithographic quality.

30 [0008] Attempts have thus been made to eliminate the need for a photographic film in the above process and in particular to obtain a printing plate directly from computer data representing the image to be reproduced. However the photosensitive coating is not sensitive enough to be directly exposed with a laser. Therefore it has been proposed to coat a silver halide layer on top of the photosensitive coating. The silver halide may then directly be exposed by means of a laser under the control of a computer. Subsequently, the silver halide layer is developed leaving a silver image on top of the photosensitive coating. That silver image then serves as a mask in an overall exposure of the photosensitive coating. After the overall exposure the silver image is removed and the photosensitive coating is developed. Such method is disclosed in for example JP-A- 60- 61 752 but has the disadvantage that a complex development and associated developing liquids are needed.

35 [0009] GB-1 492 070 discloses a method wherein a metal layer or a layer containing carbon black is provided on a photosensitive coating. This metal layer is then ablated by means of a laser so that an image mask on the photosensitive layer is obtained. The photosensitive layer is then overall exposed by UV-light through the image mask. After removal of the image mask, the photosensitive layer is developed to obtain a printing plate. This method however still has the disadvantage that the image mask has to be removed prior to development of the photosensitive layer by a cumbersome processing.

40 [0010] Furthermore methods are known for making printing plates involving the use of imaging elements that are heat-sensitive rather than photosensitive. A particular disadvantage of photosensitive imaging elements such as described above for making a printing plate is that they have to be shielded from the light. Furthermore they have a problem of sensitivity in view of the storage stability and they show a lower resolution. The trend towards heat mode printing plate precursors is clearly seen on the market.

45 [0011] For example, Research Disclosure no. 33303 of January 1992 discloses a heat mode imaging element comprising on a support a cross-linked hydrophilic layer containing thermoplastic polymer particles and an infrared absorbing pigment such as e.g. carbon black. By image-wise exposure to an infrared laser, the thermoplastic polymer particles are image-wise coagulated thereby rendering the surface of the imaging element at these areas ink-acceptant without any further development. A disadvantage of this method is that the printing plate obtained is easily damaged since the non-printing areas may become ink accepting when some pressure is applied thereto. Moreover, under critical conditions, the lithographic performance of such a printing plate may be poor and accordingly such printing plate has

lithographic printing latitude.

[0012] US-P- 4 708 925 discloses imaging elements including a photosensitive composition comprising an alkali-soluble novolac resin and an onium-salt. This composition may optionally contain an IR-sensitizer. After image-wise exposing said imaging element to UV - visible - or IR-radiation followed by a development step with an aqueous alkali liquid there is obtained a positive or negative working printing plate. The printing results of a lithographic plate obtained by irradiating and developing said imaging element are poor.

[0013] EP-A- 625 728 discloses an imaging element comprising a layer which is sensitive to UV- and IR-irradiation and which may be positive or negative working. This layer comprises a resole resin, a novolac resin, a latent Bronsted acid and an IR-absorbing substance. The printing results of a lithographic plate obtained by irradiating and developing said imaging element are poor.

[0014] US-P- 5 340 699 is almost identical with EP-A- 625 728 but discloses the method for obtaining a negative working IR-laser recording imaging element. The IR-sensitive layer comprises a resole resin, a novolac resin, a latent Bronsted acid and an IR-absorbing substance. The printing results of a lithographic plate obtained by irradiating and developing said imaging element are poor.

[0015] Furthermore EP-A- 678 380 discloses a method wherein a protective layer is provided on a grained metal support underlying a laser-ablatable surface layer. Upon image-wise exposure the surface layer is fully ablated as well as some parts of the protective layer. The printing plate is then treated with a cleaning solution to remove the residue of the protective layer and thereby exposing the hydrophilic surface layer.

[0016] EP-A- 97 200 588.8 discloses a heat mode imaging element for making lithographic printing plates comprising on a lithographic base having a hydrophilic surface an intermediate layer comprising a polymer, soluble in an aqueous alkaline solution and a top layer that is sensitive to IR-radiation wherein said top layer upon exposure to IR-radiation has a decreased or increased capacity for being penetrated and/or solubilised by an aqueous alkaline solution.

[0017] GB-A- 1 208 415 discloses a method of recording information comprising information-wise heating a recording material comprising a support bearing, with or without an inter-layer, a heat-sensitive recording layer constituted so that such information-wise heating creates a record of the information in terms of a difference in the water-permeability of different areas of the recording layer, treating the recording material with an aqueous liquid which penetrates through the water-permeable or more water permeable areas of the recording layer and is constituted so as to effect a permanent physical and/or chemical change of at least the surface portions of the underlying support or inter-layer in the corresponding areas, and removing the whole of the recording layer to expose said information-wise changed underlying support or inter-layer.

[0018] EP-A- 823 327 discloses a positive photosensitive composition showing a difference in solubility in alkali developer as between an exposed portion and a non-exposed portion, which comprises as components inducing the difference in solubility,

(a) a photo-thermal conversion material, and

(b) a high molecular compound, of which the solubility in an alkali developer is changeable mainly by a change other than a chemical change.

[0019] US-A- 5 641 608 discloses a process for the direct production of an imaged pattern of resist on a substrate, which process utilizes thermo-resist rather than photoresist, i.e. compositions which undergo thermally-induced, rather than photo-induced, chemical transformations. A film of thermo-resist composition applied to the surface substrate is scanned by a focused heat source in a predetermined pattern, without a phototool, to bring about localized thermally-induced chemical transformations of the composition which either directly produce the resist pattern or produce in the film a developable latent image of the pattern.

[0020] GB-A- 1 154 568 discloses a method of recording a graphic original having contrasting light-absorbing and light-transmitting areas, wherein a recording material comprising a supported layer composed mainly of gelatin the water-solubility or water-absorptive capacity of which increases if the layer is sufficiently heated, such layer also having light-absorbing substance(s) distributed therein, is placed with such gelatin layer in contact with the light-absorbing areas of the original and the said gelatin layer is exposed to light through the original, the intensity of the light and the duration of the exposure being such that the areas of the gelatin layer in contact with the light absorbing areas of the original are substantially unaffected by heat conduction from such light-absorbing areas, but the water solubility or water-absorptive capacity of the other areas of the gelatin layer is increased by heating thereof due to absorption of copying light by the light-absorbing substance(s) in those other areas of the gelatin layer.

[0021] GB-A-1 245 924 discloses an information-recording method wherein a recording material is used comprising a heat-sensitive recording layer of a composition such that the solubility of any given area of the layer in a given solvent can be increased by heating that area of the layer, wherein the said layer is information-wise heated to produce a record of the information in terms of a difference in the solubilities in the said solvent of different areas of the recording layer, and wherein the whole layer is then contacted with such solvent to cause the portions of the recording layer

which are soluble or most soluble in such solvent to be removed or penetrated by such solvent, the said method being characterized in that the said recording layer is wholly or mainly composed of one or more heat-sensitive polymeric compounds.

[0022] FR-A-1 561 957 discloses a process in order of registering or reproducing information by means of electromagnetic radiation and also discloses elements sensitive for heat containing substances wherein heat is produced by exposure to electromagnetic radiation.

[0023] GB-A-1 155 035 discloses a method of recording information, wherein a recording material is used comprising a layer of a polymeric material which when any given area of the layer is sufficiently heated undergoes in that area a modification resulting in a decrease in the solubility of that area of the layer in water or an aqueous medium, such layer also incorporating a substance or substances distributed over the whole area of the layer and being capable of being heated by exposing the layer to intense radiant energy which is absorbed by such substance or substances, and wherein the said material is exposed to intense radiant energy which is distributed over the material in a pattern determined by the information to be recorded and which is at least partly absorbed by said distributed substance or substances, so that a corresponding heat pattern is generated in the material, whereby such information is recorded in terms of a difference in the solubilities in water or an aqueous medium of different areas of said layer.

[0024] GB-A-1 160 221 discloses a method of recording information, wherein a recording material is used comprising a water permeable recording layer which incorporates hydrophobic thermoplastic polymeric material in the form of particles solid at room temperature and which can be rendered water-impermeable or substantially less water-permeable by the action of heat, said recording material also incorporating, in heat-conductive relationship to said polymer particles, a substance or substances which is or are distributed over the whole area of such material and is or are capable of being heated by exposing the material to intense electro-magnetic radiation which is absorbed by such substance or substances; and wherein the recording material is exposed to such an amount of electro-magnetic radiation which is absorbed by said distributed substance or substances and is distributed over the recording material in a pattern determined by the information to be recorded, that a corresponding heat pattern is generated in the recording material whereby such information is recorded in terms of a difference in the water-permeabilities of different areas of said recording layer.

[0025] EP 0 908 306 A and EP 0 908 304 A (prior art according to article 54(3) EPC) disclose a heat mode imaging element consisting of a lithographic base with a hydrophilic surface and a top layer which top layer is sensitive to IR-radiation, comprises a polymer, soluble in an aqueous alkaline solution and is unpenetrable for or insoluble in an alkaline developer containing SiO_2 as silicates

[0026] Said last three heat-mode imaging element have the disadvantage that the upper layer is very sensitive for scratches. Covering said layer with a protective layer results in a lower resolution and in a lower development latitude, due to a smaller difference in the rate of penetration of the developing liquid between exposed and non-exposed areas. A solution for said problem would be appreciated

OBJECTS OF THE INVENTION

[0027] It is an object of the invention to provide a heat mode imaging element for making a lithographic printing plate with a wide latitude of development.

[0028] It is an object of the invention to provide a heat mode imaging element for making a lithographic printing plate with a high resolution.

[0029] It is further an object of the present invention to provide a heat mode imaging element for making a lithographic printing plate with an improved scratch resistance.

[0030] Further objects of the present invention will become clear from the description hereinafter.

SUMMARY OF THE INVENTION

[0031] According to the present invention there is provided a heat mode imaging element for making a lithographic printing plate having on a lithographic base with a hydrophilic surface a first layer including a first polymer, soluble in an aqueous alkaline solution but not in water, and less than 5% by weight compared to the polymer, soluble in the aqueous alkaline solution of a hydrophilic polymer and a top layer on the same side of the lithographic base as the first layer which top layer is IR-sensitive and unpenetrable for or insoluble in an alkaline developer containing SiO_2 as silicates, wherein said first layer and said top layer may be one and the same layer; characterized in that said top layer contains a scratch resistance increasing compound selected from the group consisting of a second polymer in an amount from 30 mg to 500 mg/m^2 , a triaryl methane dye and a phthalocyanine dye.

DETAILED DESCRIPTION OF THE INVENTION

[0032] The top layer is also called the second layer.

[0033] Suitable polymers which can be used as scratch resistance increasing agents are preferably polymers with a glass transition temperature of at least 35°C, more preferably above 40°C capable of forming a film by drying at high temperature

[0034] Representative polymers which can be used as scratch resistance increasing agents are eg acrylates, self-crosslinking acrylates, acrylates in combination with melamine-hardeners. These polymers can be added as a solution to the coating but also as a dispersion to the coating.

[0035] Another class of polymers which can be used as scratch resistance increasing agents are of the type of polyvinylalcohol and modified derivatives, which can be hardened with well known hardeners of the type of orthosilicates, orthotitanates, aldehyde-type compounds,

[0036] Other polymers that can be used as scratch resistance increasing agents are polymethylmethacrylates, styrene-maleic anhydride copolymers, polycarbonates, polyamides, terpolymers of styrene-methylmethacrylate-maleic acid, selfcrosslinking terpolymers acrylates-styrene-maleic acid.

[0037] One of the preferred classes of polymers that can be used as scratch resistance increasing agents is these of the polyurethanes. Polyurethanes can be obtained from the polymerisation of following polyisocyanates and polyhydric alcohols.

[0038] As polyhydric alcohols can be used the simple polyhydric alcohols as ethylene glycol, propylene glycol, 1,3-propanediol, 1,4-butanediol, 1,4 butylene glycol, 1,5 pentanediol, 1,6 hexanediol, diethylene glycol, dipropylene glycol, neopentyl glycol, triethylene glycol, p-xylylene glycol, bisphenol A, hydrogenated bisphenol A, bisphenol dihydroxypropyl ether, glycerol, trimethylolpropane, trimethylolpropane, trishydroxymethylaminomethane, pentaerythritol, dipentaerythritol, sorbitol, sucrose, degraded starch. As polyhydric alcohols can also be used condensation polyester polyols with hydroxyl groups at both ends obtained by polycondensation between any of these polyhydric alcohols and dicarboxylic acids or anhydrides as succinic acid, the three isomeric phthalic acids, phthalic anhydride, adipic acid, hexahydrophthalic acid, isophthalic acid, hydroxy-functional polylactons produced by transesterification of diphenyl carbonate with glycols. Another process for manufacturing hydroxyl-terminated polyesters include ring-opening polymerisation of ϵ -caprolactone in the presence of glycol.

[0039] As isocyanates can be used the following compounds:

hexamethylene diisocyanate, trimethylhexamethylene diisocyanate, diphenyl ether isocyanate, dimeric acid diisocyanate, bicycloheptane triisocyanate, paraphenylene diisocyanate, 2,4- or 2,6-toluylene diisocyanate, 4,4-diphenylmethane diisocyanate, tolidine diisocyanate, hydrogenated xylylene diisocyanate, cyclohexane diisocyanate, metaxylylene diisocyanate, 2,6-diisocyanate methylcaproate, 4,4'-methylenebis(cyclohexylisocyanate), methylcyclohexane 2,4(2,6)diisocyanate, 1,3-(isocyanatomethyl)cyclohexane, isophorone diisocyanate, tetramethylxylylene diisocyanate, polymethylenepolyphenyl isocyanate, triaryl methane triisocyanate, tris(isocyanatophenyl) thiophosphate, tetramethylxylylene diisocyanate, lysine ester triisocyanate, 1,6,11-undecane triisocyanate, 1,8-diisocyanato-4-isocyanatomethyloctane, 1,3,6-hexamethylene triisocyanate,...

[0040] The above mentioned polyurethanes can be hardened with melamine-derivates. As a preferred melamine derivate can be used a methylated melamine-formaldehyde reaction product. For the hardening of these systems the addition of strong acids functions as catalyst.

[0041] Said urethanes are used in an amount preferably between 30 and 200 mg/m².

[0042] Another preferred class of polymers that can be used as scratch resistance increasing agents is these of cellulose and derivatives. As nitrocellulose can be used the esterified product of cellulose with nitrating acid with a nitrogen content of the final product lower than 12.6%. As cellulose can be used natural cellulose.

[0043] Said celluloses are used in an amount preferably between 30 and 120 mg/m².

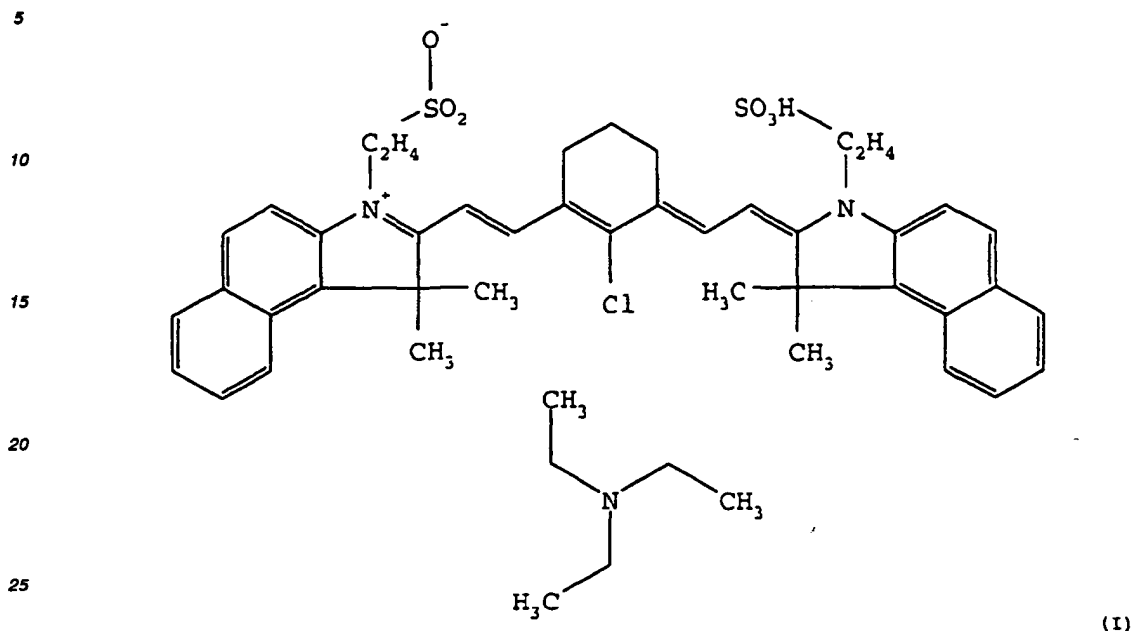
[0044] The triaryl methane dyes are used preferably in an amount ranging from 30 to 500 mg, more preferably in an amount between 50 and 200 mg/m².

[0045] The phthalocyanine dyes can be metal containing dyes or metal-free dyes. They are used preferably in an amount ranging from 40 to 600 mg, more preferably in an amount between 80 and 250 mg/m².

[0046] In a first embodiment the first layer and the top layer are different. In said embodiment there is provided a heat mode imaging element for making lithographic printing plates having on a lithographic base with a hydrophilic surface a first layer including a polymer, soluble in an aqueous alkaline solution but not in water and a top layer on the same side of the lithographic base as the first layer which top layer is sensitive to IR-radiation and which is unpenetrable for or insoluble in an alkaline developer containing SiO₂ as silicates.

[0047] The top layer, in accordance with the present invention comprises a second polymer an IR-dye or pigment, as mentioned in claim 1, and preferably also a binder resin. A mixture of IR-dyes or pigments may be used, but it is preferred to use only one IR-dye or pigment. Preferably said IR-dyes are IR-cyanine dyes. Particularly useful IR-cyanine dyes are cyanine dyes with at least two acid groups, more preferably with at least two sulphonic groups. Still

more preferably are cyanine dyes with two indolenine and at least two sulphonic acid groups. Most preferably is compound I with the structure as indicated



Particularly useful IR-absorbing pigments are carbon black, metal carbides, borides, nitrides, carbonitrides, bronze-structured oxides and oxides structurally related to the bronze family but lacking the A component e.g. WO₂. It is also possible to use conductive polymer dispersion such as polypyrrole or polyaniline-based conductive polymer dispersions. The lithographic performance and in particular the print endurance obtained depends on the heat-sensitivity of the imaging element. In this respect it has been found that carbon black yields very good and favorable results.

[0048] The IR-absorbing dyes or pigments are present preferably in an amount between 1 and 99 parts, more preferably between 50 and 95 parts by weight of the total amount of said IR-sensitive top layer.

[0049] The top layer may preferably comprise as binder a water insoluble polymer such as a cellulose ester, a copolymer of vinylidene chloride and acrylonitrile, poly(meth)acrylates, polyvinyl chloride, silicone resins, etc. Preferred as binder is nitrocellulose resin.

[0050] The total amount of the top layer preferably ranges from 0.05 to 10 g/m², more preferably from 0.1 to 2 g/m².

[0051] In the top layer a difference in the capacity of being penetrated and/or solubilised by the aqueous alkaline solution is generated upon image-wise exposure for an alkaline developer according to the invention.

[0052] In the present invention the said capacity is increased upon image-wise IR exposure to such degree that the imaged parts will be cleaned out during development without solubilising and/or damaging the non-imaged parts.

[0053] The development with the aqueous alkaline solution is preferably done within an interval of 5 to 120 seconds.

[0054] Between the top layer and the lithographic base the present invention comprises a first layer soluble in an aqueous alkaline developing solution with preferentially a pH between 7.5 and 14. Said layer is preferably contiguous to the top layer but other layers may be present between the top layer and the first layer. The alkali soluble binders used in this layer are preferably hydrophobic binders as used in conventional positive or negative working PS-plates e.g. novolac polymers, polymers containing hydroxystyrene units, carboxy substituted polymers etc. Typical examples of these polymers are described in DE-A- 4 007 428, DE-A- 4 027 301 and DE-A- 4 445 820.

[0055] Furthermore this aqueous alkali soluble layer is preferably a visible light- and UV-light desensitised layer. Said layer is preferably thermally hardenable. This preferably visible light- and UV-desensitised layer does not comprise photosensitive ingredients such as diazo compounds, photoacids, photoinitiators, quinone diazides, sensitizers etc. which absorb in the wavelength range of 250nm to 650nm. In this way a daylight stable printing plate may be obtained.

[0056] Said first layer preferably also includes a low molecular acid, preferably a carboxylic acid, still more preferably a benzoic acid, most preferably 3,4,5-trimethoxybenzoic acid or a benzophenone.

[0057] The ratio between the total amount of low molecular acid or benzophenone and polymer in the first layer preferably ranges from 2:98 to 40:60, more preferably from 5:95 to 20:80. The total amount of said first layer preferably

ranges from 0.1 to 10 g/m², more preferably from 0.3 to 2 g/m².

[0058] In the imaging element according to the present invention, the lithographic base may be an anodised aluminum for all embodiments. A particularly preferred lithographic base is an electrochemically grained and anodised aluminum support. The anodised aluminum support may be treated to improve the hydrophilic properties of its surface. For example, the aluminum support may be silicated by treating its surface with sodium silicate solution at elevated temperature, e.g. 95°C. Alternatively, a phosphate treatment may be applied which involves treating the aluminum oxide surface with a phosphate solution that may further contain an inorganic fluoride. Further, the aluminum oxide surface may be rinsed with a citric acid or citrate solution. This treatment may be carried out at room temperature or may be carried out at a slightly elevated temperature of about 30 to 50°C. A further interesting treatment involves rinsing the aluminum oxide surface with a bicarbonate solution. Still further, the aluminum oxide surface may be treated with polyvinylphosphonic acid, polyvinylmethylphosphonic acid, phosphoric acid esters of polyvinyl alcohol, polyvinylsulphonic acid, polyvinylbenzenesulphonic acid, sulphuric acid esters of polyvinyl alcohol, and acetals of polyvinyl alcohols formed by reaction with a sulphonated aliphatic aldehyde. It is further evident that one or more of these post treatments may be carried out alone or in combination. More detailed descriptions of these treatments are given in GB-A-1 084 070, DE-A-4 423 140, DE-A-4 417 907, EP-A-659 909, EP-A-537 633, DE-A-4 001 466, EP-A-292 801, EP-A-291 760 and US-P-4 458 005.

[0059] According to another mode in connection with the present invention, the lithographic base having a hydrophilic surface comprises a flexible support, such as e.g. paper or plastic film, provided with a cross-linked hydrophilic layer for all embodiments. A particularly suitable cross-linked hydrophilic layer may be obtained from a hydrophilic binder cross-linked with a cross-linking agent such as formaldehyde, glyoxal, polyisocyanate or a hydrolysed tetra-alkylorthosilicate. The latter is particularly preferred.

[0060] As hydrophilic binder there may be used hydrophilic (co)polymers such as for example, homopolymers and copolymers of vinyl alcohol, acrylamide, methylol acrylamide, methylol methacrylamide, acrylate acid, methacrylate acid, hydroxyethyl acrylate, hydroxyethyl methacrylate or maleic anhydride/vinylmethylether copolymers. The hydrophilicity of the (co)polymer or (co)polymer mixture used is preferably the same as or higher than the hydrophilicity of polyvinyl acetate hydrolyzed to at least an extent of 60 percent by weight, preferably 80 percent by weight.

[0061] The amount of crosslinking agent, in particular of tetraalkyl orthosilicate, is preferably at least 0.2 parts by weight per part by weight of hydrophilic binder, more preferably between 0.5 and 5 parts by weight, most preferably between 1.0 parts by weight and 3 parts by weight.

[0062] A cross-linked hydrophilic layer in a lithographic base used in accordance with the present embodiment preferably also contains substances that increase the mechanical strength and the porosity of the layer. For this purpose colloidal silica may be used. The colloidal silica employed may be in the form of any commercially available water-dispersion of colloidal silica for example having an average particle size up to 40 nm, e.g. 20 nm. In addition inert particles of larger size than the colloidal silica may be added e.g. silica prepared according to Stöber as described in J. Colloid and Interface Sci., Vol. 26, 1968, pages 62 to 69 or alumina particles or particles having an average diameter of at least 100 nm which are particles of titanium dioxide or other heavy metal oxides. By incorporating these particles the surface of the cross-linked hydrophilic layer is given a uniform rough texture consisting of microscopic hills and valleys, which serve as storage places for water in background areas.

[0063] The thickness of a cross-linked hydrophilic layer in a lithographic base in accordance with this embodiment may vary in the range of 0.2 to 25 µm and is preferably 1 to 10 µm.

[0064] Particular examples of suitable cross-linked hydrophilic layers for use in accordance with the present invention are disclosed in EP-A-601 240, GB-P-1 419 512, FR-P-2 300 354, US-P-3 971 660, US-P-4 284 705 and EP-A-514 490.

[0065] As flexible support of a lithographic base in connection with the present embodiment it is particularly preferred to use a plastic film e.g. substrated polyethylene terephthalate film, substrated polyethylene naphthalate film, cellulose acetate film, polystyrene film, polycarbonate film etc... The plastic film support may be opaque or transparent.

[0066] It is particularly preferred to use a polyester film support to which an adhesion improving layer has been provided. Particularly suitable adhesion improving layers for use in accordance with the present invention comprise a hydrophilic binder and colloidal silica as disclosed in EP-A-619 524, EP-A-620 502 and EP-A-619 525. Preferably, the amount of silica in the adhesion improving layer is between 200 mg per m² and 750 mg per m². Further, the ratio of silica to hydrophilic binder is preferably more than 1 and the surface area of the colloidal silica is preferably at least 300 m² per gram, more preferably at least 500 m² per gram.

[0067] In a second embodiment the first layer and the second layer are the same. In said embodiment there is provided a heat mode imaging element for making lithographic printing plates having on a lithographic base with a hydrophilic surface a top layer which top layer is sensitive to IR-radiation, comprises a polymer, soluble in an aqueous alkaline solution and is unpenetrable for or insoluble in an alkaline developer containing SiO₂ as silicates.

[0068] The IR-sensitive layer, in accordance with the present invention comprises an IR-dye or pigment and a polymer, soluble in an aqueous alkaline solution. A mixture of IR-dyes or pigments may be used, but it is preferred to use

only on IR-dye or pigment. Suitable IR-dyes and pigments are those mentioned above in the first embodiment of the present invention.

[0069] The IR-dyes are present preferably in an amount between 1 and 60 parts, more preferably between 3 and 50 parts by weight of the total amount of said IR-sensitive top layer.

[0070] The alkali soluble polymers used in this layer are preferably hydrophobic and ink accepting polymers as used in conventional positive or negative working PS-plates e.g. carboxy substituted polymers etc. More preferably is a phenolic resin such as a hydroxystyrene units containing polymer or a novolac polymer. Most preferred is a novolac polymer. Typical examples of these polymers are described in DE-A-4 007 428, DE-A-4 027 301 and DE-A-4 445 820.

[0071] Furthermore this IR-sensitive layer is preferably a visible light- and UV-light desensitised layer. Still further said layer is preferably thermally hardenable. This preferably visible light- and UV-light desensitised layer does not comprise photosensitive ingredients such as diazo compounds, photoacids, photoinitiators, quinone diazides, sensitizers etc. which absorb in the wavelength range of 250nm to 650nm. In this way a daylight stable printing plate may be obtained.

[0072] Said IR-sensitive layer preferably also includes a low molecular acid, more preferably a carboxylic acid, still more preferably a benzoic acid, most preferably 3,4,5-trimethoxybenzoic acid or a benzofenone, more preferably trihydroxybenzofenone.

[0073] The ratio between the total amount of low molecular acid or benzofenone and polymer in the IR-sensitive layer preferably ranges from 2:98 to 40:60, more preferably from 5:95 to 30:70. The total amount of said IR-sensitive layer preferably ranges from 0.1 to 10 g/m², more preferably from 0.3 to 2 g/m².

[0074] In the IR-sensitive layer a difference in the capacity of being penetrated and/or solubilised by the alkaline developer is generated upon image-wise exposure for an alkaline developer according to the invention.

[0075] To prepare a lithographic plate, the heat-mode imaging element is image-wise exposed and developed.

[0076] Image-wise exposure in connection with the present invention is an image-wise scanning exposure involving the use of a laser that operates in the infrared or near-infrared, i.e. wavelength range of 700-1500 nm. Most preferred are laser diodes emitting in the near-infrared. Exposure of the imaging element may be performed with lasers with a short as well as with lasers with a long pixel dwell time. Preferred are lasers with a pixel dwell time between 0.005 μ s and 20 μ s.

[0077] After the image-wise exposure the heat mode imaging element is developed by rinsing it with an aqueous alkaline solution. The aqueous alkaline solutions used in the present invention are those that are used for developing conventional positive working presensitised printing plates, preferably containing SiO₂ as silicates and having preferably a pH between 11.5 and 14. Thus the imaged parts of the top layer that were rendered more penetrable for the aqueous alkaline solution upon exposure are cleaned-out whereby a positive working printing plate is obtained.

[0078] In the present invention, the composition of the developer used is also very important.

[0079] Therefore, to perform development processing stably for a long time period particularly important are qualities such as strength of alkali and the concentration of silicates in the developer. Under such circumstances, the present inventors have found that a rapid high temperature processing can be performed, that the amount of the replenisher to be supplemented is low and that a stable development processing can be performed over a long time period of the order of not less than 3 months without exchanging the developer only when the developer having the foregoing composition is used.

[0080] The developers and replenishers for developer used in the invention are preferably aqueous solutions mainly composed of alkali metal silicates and alkali metal hydroxides represented by MOH or their oxide, represented by M₂O, wherein said developer comprises SiO₂ of 0.5 to 1.5 and a concentration of SiO₂ of 0.5 to 5% by weight. As such alkali metal silicates, preferably used are, for instance, sodium silicate, potassium silicate, lithium silicate and sodium metasilicate. On the other hand, as such alkali metal hydroxides, preferred are sodium hydroxide, potassium hydroxide and lithium hydroxide.

[0081] The developers used in the invention may simultaneously contain other alkaline agents. Examples of such other alkaline agents include such inorganic alkaline agents as ammonium hydroxide, sodium tertiary phosphate, sodium secondary phosphate, potassium tertiary phosphate, potassium secondary phosphate, ammonium tertiary phosphate, ammonium secondary phosphate, sodium bicarbonate, sodium carbonate, potassium carbonate and ammonium carbonate; and such organic alkaline agents as mono-, di- or triethanolamine, mono-, di- or trimethylamine, mono-, di- or triethylamine, mono- or di-isopropylamine, n-butylamine, mono-, di- or triisopropanolamine, ethyleneimine, ethylenediimine and tetramethylammonium hydroxide.

[0082] In the present invention, particularly important is the molar ratio in the developer of [SiO₂] / [M₂O], which is generally 0.6 to 1.5, preferably 0.7 to 1.3. This is because if the molar ratio is less than 0.6, great scattering of activity is observed, while if it exceeds 1.5, it becomes difficult to perform rapid development and the dissolving out or removal of the light-sensitive layer on non-image areas is liable to be incomplete. In addition, the concentration of SiO₂ in the developer and replenisher preferably ranges from 1 to 4 % by weight. Such limitation of the concentration of SiO₂ makes it possible to stably provide lithographic printing plates having good finishing qualities even when a large amount

of plates according to the invention are processed for a long time period.

[0083] In a particular preferred embodiment, an aqueous solution of an alkali metal silicate having a molar ratio $[\text{SiO}_2] / [\text{M}_2\text{O}]$, which ranges from 1.0 to 1.5 and a concentration of SiO_2 of 1 to 4 % by weight is used as a developer. In such cases, it is a matter of course that a replenisher having alkali strength equal to or more than that of the developer is employed. In order to decrease the amount of the replenisher to be supplied, it is advantageous that a molar ratio, $[\text{SiO}_2] / [\text{M}_2\text{O}]$, of the replenisher is equal to or smaller than that of the developer, or that a concentration of SiO_2 is high if the molar ratio of the developer is equal to that of the replenisher.

[0084] In the developers and the replenishers used in the invention, it is possible to simultaneously use organic solvents having solubility in water at 20 °C of not more than 10 % by weight according to need. Examples of such organic solvents are such carboxylic acid esters as ethyl acetate, propyl acetate, butyl acetate, amyl acetate, benzyl acetate, ethylene glycol monobutyl acetate, butyl lactate and butyl levulinate; such ketones as ethyl butyl ketone, methyl isobutyl ketone and cyclohexanone; such alcohols as ethylene glycol monobutyl ether, ethylene glycol benzyl ether, ethylene glycol monophenyl ether, benzyl alcohol, methylphenylcarbinol, n-amyl alcohol and methylamyl alcohol; such alkyl-substituted aromatic hydrocarbons as xylene; and such halogenated hydrocarbons as methylene dichloride and monochlorobenzene. These organic solvents may be used alone or in combination. Particularly preferred is benzyl alcohol in the invention. These organic solvents are added to the developer or replenisher therefor generally in an amount of not more than 5 % by weight and preferably not more than 4 % by weight.

[0085] The developers and replenishers used in the present invention may simultaneously contain a surfactant for the purpose of improving developing properties thereof. Examples of such surfactants include salts of higher alcohol (C8 ~ C22) sulfuric acid esters such as sodium salt of lauryl alcohol sulfate, sodium salt of octyl alcohol sulfate, ammonium salt of lauryl alcohol sulfate, Teepol B-81 (trade mark, available from Shell Chemicals Co., Ltd.) and disodium alkyl sulfates; salts of aliphatic alcohol phosphoric acid esters such as sodium salt of cetyl alcohol phosphate; alkyl aryl sulfonic acid salts such as sodium salt of dodecylbenzene sulfonate, sodium salt of isopropyl naphthalene sulfonate, sodium salt of dinaphthalene disulfonate and sodium salt of metanitrobenzene sulfonate; sulfonic acid salts of alkylamides such as $\text{C}_{17}\text{H}_{33}\text{CON}(\text{CH}_3)\text{CH}_2\text{CH}_2\text{SO}_3\text{Na}$ and sulfonic acid salts of dibasic aliphatic acid esters such as sodium dioctyl sulfosuccinate and sodium dihexyl sulfosuccinate. These surfactants may be used alone or in combination. Particularly preferred are sulfonic acid salts. These surfactants may be used in an amount of generally not more than 5 % by weight and preferably not more than 3 % by weight.

[0086] In order to enhance developing stability of the developers and replenishers used in the invention, the following compounds may simultaneously be used.

[0087] Examples of such compounds are neutral salts such as NaCl, KCl and KBr as disclosed in JN-A- 58- 75 152; chelating agents such as EDTA and NTA as disclosed in JN-A- 58- 190 952 (U.S.-A- 4 469 776), complexes such as $[\text{Co}(\text{NH}_3)_6]\text{Cl}_3$ as disclosed in JN-A- 59- 121 336 (US-A- 4 606 995); ionizable compounds of elements of the group IIa, IIIa or IIIb of the Periodic Table such as those disclosed in JN-A- 55- 25 100; anionic or amphoteric surfactants such as sodium alkyl naphthalene sulfonate and N-tetradecyl-N,N-dihydroxyethyl betaine as disclosed in JN-A- 50- 51 324; tetramethyldecyne diol as disclosed in US-A- 4 374 920; non-ionic surfactants as disclosed in JN-A- 60- 213 943; cationic polymers such as methyl chloride quaternary products of p-dimethylaminomethyl polystyrene as disclosed in JN-A- 55- 95 946; amphoteric polyelectrolytes such as copolymer of vinylbenzyl trimethylammonium chloride and sodium acrylate as disclosed in JN-A- 56- 142 528; reducing inorganic salts such as sodium sulfite as disclosed in JN-A- 57- 192 952 (US-A- 4 467 027) and alkaline-soluble mercapto compounds or thioether compounds such as thiosalicylic acid, cysteine and thioglycolic acid; inorganic lithium compounds such as lithium chloride as disclosed in JN-A- 58- 59 444; organic lithium compounds such as lithium benzoate as disclosed in JN-A- 50 34 442; organometallic surfactants containing Si, Ti or the like as disclosed in JN-A- 59- 75 255; organoboron compounds as disclosed in JN-A- 59- 84 241 (US-A- 4 500 625); quaternary ammonium salts such as tetraalkylammonium oxides as disclosed in EP-A- 101 010; and bactericides such as sodium dehydroacetate as disclosed in JN-A- 63- 226 657.

[0088] In the method for development processing of the present invention, any known means of supplementing a replenisher for developer may be employed. Examples of such methods preferably used are a method for intermittently or continuously supplementing a replenisher as a function of the amount of PS plates processed and time as disclosed in JN-A- 55- 115 039 (GB-A- 2 046 931), a method comprising disposing a sensor for detecting the degree of light-sensitive layer dissolved out in the middle portion of a developing zone and supplementing the replenisher in proportion to the detected degree of the light-sensitive layer dissolved out as disclosed in JN-A- 58- 95 349 (US-A- 4 537 496); a method comprising determining the impedance value of a developer and processing the detected impedance value by a computer to perform supplementation of a replenisher as disclosed in GB-A- 2 208 249.

[0089] The printing plate of the present invention can also be used in the printing process as a seamless sleeve printing plate. In this option the printing plate is soldered in a cylindrical form by means of a laser. This cylindrical printing plate which has as diameter the diameter of the print cylinder is slid on the print cylinder instead of applying in a classical way a classically formed printing plate. More details on sleeves are given in "Grafisch Nieuws" ed. Keising, 15, 1995, page 4 to 6.

[0090] After the development of an image-wise exposed imaging element with an aqueous alkaline solution and drying, the obtained plate can be used as a printing plate as such. However, to improve durability it is still possible to bake said plate at a temperature between 200°C and 300°C for a period of 30 seconds to 5 minutes. Also the imaging element can be subjected to an overall post-exposure to UV-radiation to harden the image in order to increase the run length of the printing plate.

[0091] The following examples illustrate the present invention without limiting it thereto. All parts and percentages are by weight unless otherwise specified.

EXAMPLE 1 (Comparative example)

Preparation of the lithographic base

[0092] A 0.30 mm thick aluminum foil was degreased by immersing the foil in an aqueous solution containing 5 g/l of sodium hydroxide at 50°C and rinsed with demineralized water. The foil was then electrochemically grained using an alternating current in an aqueous solution containing 4 g/l of hydrochloric acid, 4 g/l of hydroboric acid and 5 g/l of aluminum ions at a temperature of 35°C and a current density of 1200 A/m² to form a surface topography with an average center-line roughness Ra of 0.5 mm.

[0093] After rinsing with demineralized water the aluminum foil was then etched with an aqueous solution containing 300 g/l of sulfuric acid at 60°C for 180 seconds and rinsed with demineralized water at 25°C for 30 seconds.

[0094] The foil was subsequently subjected to anodic oxidation in an aqueous solution containing 200 g/l of sulfuric acid at a temperature of 45°C, a voltage of about 10 V and a current density of 150 A/m² for about 300 seconds to form an anodic oxidation film of 3.00 g/m² of Al₂O₃ then washed with demineralized water, posttreated with a solution containing polyvinylphosphonic acid and subsequently with a solution containing aluminum trichloride, rinsed with demineralized water at 20°C during 120 seconds and dried.

Preparation of the heat-mode imaging element 1

[0095] On the above described lithographic base was first coated a layer from an 8.6% wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14 µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.

Upon this layer was then coated with a wet coating thickness of 20 µm, the IR-sensitive layer from a 0.735%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.

The resulting IR-sensitive layer contained 115 mg/m² of carbon black 11.5 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

EXAMPLE 2

[0096] On the lithographic base described in example 1, was first coated a layer from an 8.6% wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14 µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.

Upon this layer was then coated with a wet coating thickness of 20 µm, the IR-sensitive layer from a 1.0520%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.

The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 63.0 mg/m² of ALMACRYL XPE-1676, 11.5 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410. ALMACRYL XPE-1676® is a urethane modified polyester commercially available from Image Polymers Europe.

EXAMPLE 3

[0097] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14 µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.

Upon this layer was then coated with a wet coating thickness of 20 µm, the IR-sensitive layer from a 1.3057%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds. The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 114.1 mg/m² of ALMACRYL XPE-1676, 11.5 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego

Wet 265 and 5.0 mg/m² of Tego Glid 410.

EXAMPLE 4

- 5 [0098] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.
- Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 1.052%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least
- 10 40 seconds. The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 43.7 mg/m² of ALMACRYL XPE-1676, 11.5 mg/m² of nitrocellulose, 18.9 mg/m² of CYMEL 303, 0.63 mg/m² of p-toluene sulphonic acid, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410. CYMEL 303® is a methylated melamine-formaldehyde crosslinking agent commercial available from CYANAMID.

15 EXAMPLE 5 (Comparative example)

- [0099] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.
- 20 Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 0.777%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.
- The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 20 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

25 EXAMPLE 6

- [0100] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.
- 30 Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 0.927%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.
- The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 50 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

EXAMPLE 7

- [0101] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.
- 40 Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 1.177%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.
- 45 The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 100 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

EXAMPLE 8

- 50 [0102] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.
- Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 1.177%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least
- 55 40 seconds.
- The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 11.5 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 100 mg/m² of HELIOGEN BLAU D7565, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

HELIOGEN BLAU D7565 also named C.I. Pigment Blue 16 is a copper and chlorid free phtalocyanin dye, commercially available from BASF.

EXAMPLE 9

[0103] On the lithographic base described in example 1, was first coated a layer from an 8.6%wt solution in tetrahydrofuran/methoxypropanol 55/45 ratio, with a wet coating thickness of 14µm. The resulting layer contained 88% of Alnovol SPN452 and 12% of 3,4,5-trimethoxybenzoic acid.

Upon this layer was then coated with a wet coating thickness of 20µm, the IR-sensitive layer from a 1.177%wt solution in methylethylketone/methoxypropanol 50/50 ratio. This layer was dried at a temperature of at least 120°C for at least 40 seconds.

The resulting IR-sensitive layer contained 115 mg/m² of carbon black, 11.5 mg/m² of nitrocellulose, 2.1 mg/m² of Solsperse 5000, 11.3 mg/m² of Solsperse 28000, 100 mg/m² of BASONYL BLAU 633, 2.0 mg/m² of Tego Wet 265 and 5.0 mg/m² of Tego Glide 410.

BASONYL BLAU 633 also named C.I. Basic Blue 8, is a triarylmethane dye, commercially available from BASF.

Scratching the heat-mode imaging element

[0104] The above mentioned materials in comparative example 1 and examples 2 till 9 were scratched in the test 'Linimark'. In this test scratches are formed by displacing needles at a speed of 96 cm/min, under well defined loads. The needles are of type robin with a radius of 1.5 mm. 15 scratches are formed under following loads: 57 - 85 - 114 - 142 - 170 - 113 - 169 - 225 - 282 - 338 - 400 - 600 - 800 - 1000 en 1200 mN.

After creation of the 15 scratches the material was exposed.

Exposing the heat-mode imaging element

[0105] All the above mentioned materials were imaged with a Creo 3244™ external drum platesetter at 263 mJ/cm² and 2400 dpi.

Developing the imagewise exposed element

[0106] After exposure of the imaging element, the element was developed in an aqueous alkaline developing solution. These developing was carried out in a Technigraph NPX-32 processor at a speed of 1 m/min at 25°C, filled with Ozasol EP262A (Ozasol EP262A is commercially available from Agfa) and with water in the rinsing section and Ozasol RC795 gum in the gumming section. The obtained printing plate has an intact image without etching defects.

Evaluation of the scratch resistance

[0107] The 15 scratches are controlled on width of damage and given a corresponding quotation as indicated in table 1.

When the depth of the scratch is unto the support, this means the total layer is removed, an extra value is summated. This phenomenon is visible by a discoloration from black to white metallic color on the scratch region. This value is 3 when the discoloration is locally. When the entire scratch is white a value of 5 is added.

Table 1:

Quotation	Width of scratch
0	no scratch visible
0.5	scratch smaller than 50µm
1	width between 50 and 100 µm
2	width between 100 and 150 µm
3	width between 150 and 200 µm
4	width greater than 200 µm
+ 3	when scratch is broken white line
+ 5	when scratch is fully white

[0108] A summation of all given quotations results in the scratch resistance of the material. The lower the value, the better the scratch resistance.

Evaluation of Lithographic quality of the material

[0109] After evaluation of the scratch resistance of the above mentioned materials, the plates are printed on a Heidelberg GTO46 printing machine with a conventional ink (K+E) and fountain solution (Rotamatic). The prints are evaluated on scumming in the IR-exposed areas and on good ink-uptake in the non-imaged areas.

Results

[0110]

Example	scratch resistance	Print quality
Comp 1	22	OK
Ex 2	19	OK
Ex 3	18	OK
Ex 4	14.5	OK
Ex 5	22	OK
Ex 6	15	OK
Ex 7	11	Light Scumming
Ex 8	18.5	OK
Ex 9	19	OK

Print quality OK means: no visible scumming on non-image parts and good ink-uptake.

[0111] It is seen from the examples that examples 2 to 4 and 6 to 9 (examples according to the invention) yield (much) better scratch resistance than the comparative examples 1 and 5

Claims

1. A heat mode imaging element for making a lithographic printing plate having on a lithographic base with a hydrophilic surface a first layer including a first polymer, soluble in an aqueous alkaline solution but not in water, and less than 5% by weight compared to the polymer soluble in the aqueous alkaline solution of a hydrophilic polymer and a top layer on the same side of the lithographic base as the first layer which top layer is IR-sensitive and unpenetrable for or insoluble in an alkaline developer containing SiO₂ as silicates, wherein said first layer and said top layer may be one and the same layer; characterized in that said top layer contains a scratch resistance increasing compound selected from the group consisting of a second polymer in an amount from 30 mg to 500 mg/m², a triaryl methane dye and a phthalocyanine dye.
2. A heat mode imaging element for making a lithographic printing plate according to claim 1 wherein the IR-sensitive layer contains carbon black.
3. A heat mode imaging element for making a lithographic printing plate according to claim 1 or 2 wherein the second polymer has a glass transition temperature of at least 35°C, and is capable of forming a film by drying at high temperature.
4. A heat mode imaging element for making a lithographic printing plate according to claim 3 wherein said second

polymer is a polyurethane.

- 5 5. A heat mode imaging element for making a lithographic printing plate according to claim 4 wherein said polyurethane has been hardened with a melamine.
6. A heat mode imaging element for making a lithographic printing plate according to any of claims 1 to 3 wherein said second polymer is cellulose or a cellulose derivative.
- 10 7. A heat mode imaging element for making a lithographic printing plate according to any of claims 1 to 6 wherein the first polymer is a novolac polymer or a polymer containing polyhydroxystyrene units.
8. A method for making a lithographic printing plate comprising the steps of
 - 15 a) exposing imagewise to IR-laser radiation a heat mode imaging element according to any of claims 1 to 7; and
 - b) developing said imagewise exposed heat mode imaging element with said alkaline developer whereby the exposed areas of the first and the top layer, which may be the same, are dissolved and the unexposed areas of the first layer remain undissolved.

20 Patentansprüche

1. Ein wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte, das auf einem lithografischen Träger mit einer hydrophilen Oberfläche eine erste Schicht mit einem ersten, in einer wäßrig-alkalischen Lösung löslichen, aber wasserunlöslichen Polymer und weniger als 5 Gew.-%, bezogen auf das in der wäßrig-alkalischen Lösung lösliche Polymer, eines hydrophilen Polymers und auf der gleichen Seite des lithografischen Trägers wie die erste Schicht eine Deckschicht enthält, die empfindlich gegenüber Infrarotstrahlung ist und undurchdringbar für oder unlöslich in einem SiO₂ als Silikate enthaltenden Entwickler ist, wobei die erste Schicht und die Deckschicht ein und dieselbe Schicht sein können, **dadurch gekennzeichnet, daß** die Deckschicht eine die Kratzfestigkeit verbessernde Verbindung aus der Gruppe bestehend aus einem zweiten Polymer in einer Menge zwischen 30 mg und 500 mg/m², einem Triarylmethanfarbstoff und einem Phthalocyaninfarbstoff enthält.
2. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach Anspruch 1, **dadurch gekennzeichnet, daß** die IR-empfindliche Schicht Gasruß enthält.
- 35 3. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach Anspruch 1 oder 2, **dadurch gekennzeichnet, daß** das zweite Polymer einen Einfrierpunkt von zumindest 35°C aufweist und bei Trocknung bei hoher Temperatur filmbildend sein kann.
- 40 4. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach Anspruch 3, **dadurch gekennzeichnet, daß** das zweite Polymer ein Polyurethan ist.
5. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach Anspruch 4, **dadurch gekennzeichnet, daß** das Polyurethan mit einem Melaminhärter gehärtet ist.
- 45 6. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach einem der Ansprüche 1 bis 3, **dadurch gekennzeichnet, daß** das zweite Polymer Cellulose oder ein Cellulose-Derivat ist.
7. Wärmeempfindliches Bilderzeugungselement zur Herstellung einer lithografischen Druckplatte nach einem der Ansprüche 1 bis 6, **dadurch gekennzeichnet, daß** das erste Polymer ein Novolakpolymer oder ein Polyhydroxystyroleinheiten enthaltendes Polymer ist.
- 50 8. Ein durch die nachstehenden Schritte gekennzeichnetes Verfahren zur Herstellung einer lithografischen Druckplatte :
 - 55 a) bildmäßige Belichtung mit IR-Laserstrahlung eines wärmeempfindlichen Bilderzeugungselements nach einem der Ansprüche 1 bis 7, und
 - b) Entwicklung des bildmäßig belichteten wärmeempfindlichen Bilderzeugungselements mit dem alkalischen Entwickler, wobei die belichteten Bereiche der ersten Schicht und der Deckschicht, die in und dieselbe Schicht

sein können, gelöst werden und die nicht-belichteten Bereiche der ersten Schicht ungelöst bleiben.

Revendications

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1. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique possédant sur une base lithographique munie d'une surface hydrophile une première couche renfermant un premier polymère qui est soluble dans une solution alcaline aqueuse mais pas dans de l'eau, et moins de 5 % en poids d'un polymère hydrophile par rapport au polymère soluble dans la solution alcaline aqueuse, et sur la même face de la base lithographique que la première couche une couche supérieure qui est sensible à l'infrarouge et impré-
nétrable pour ou insoluble dans un révélateur alcalin contenant du SiO₂ comme silicates, dans lequel ladite première couche et ladite couche supérieure peuvent être une seule et même couche ; **caractérisé en ce que** ladite couche supérieure contient un composé augmentant la résistance aux rayures choisi dans le groupe constitué par un second polymère en une quantité de 30 mg à 500 mg/m², un colorant de triarylméthane et un colorant de phtalocyanine.
2. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique selon la revendication 1, **caractérisé en ce que** la couche sensible à l'infrarouge contient du noir de carbone.
3. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographiquée selon la revendication 1 ou 2, **caractérisé en ce que** le second polymère possède une température de vitrification d'au moins 35°C et est capable de former un film en séchant à une température élevée.
4. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique selon la revendication 3, **caractérisé en ce que** le second polymère est un polyuréthane.
5. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique selon la revendication 4, **caractérisé en ce que** ledit polyuréthane a été durci avec de la mélamine.
6. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique selon l'une quelconque des revendications 1 à 3, **caractérisé en ce que** le second polymère est de la cellulose ou un dérivé de cellulose.
7. Un élément formateur d'image thermosensible pour la confection d'une plaque d'impression lithographique selon l'une quelconque des revendications 1 à 6, **caractérisé en ce que** le premier polymère est un polymère de novolaque ou un polymère contenant des unités de polyhydroxystyrène.
8. Un procédé pour faire une plaque d'impression lithographique comprenant les phases consistant à
 - (a) exposer en forme d'image à un rayonnement infrarouge par laser un élément formateur d'image thermosensible selon l'une quelconque des revendications 1 à 7 ; et
 - (b) développer l'élément formateur d'image thermosensible exposé en forme d'image avec le révélateur alcalin, suite à quoi les zones exposées de la première couche et de la couche supérieure, qui peuvent constituer une seule et même couche, sont dissoutes et les zones non exposées de la première couche ne sont pas dissoutes.

